Amendments to the Claims:

The following listing of claims will replace all prior versions, and listings, of claims in the application:

1. (Currently Amended) A hole transport material to be used for a layer having the function of transporting holes in an organic EL device, the hole transport material being poly(3,4-ethylenedioxythiophene/styrenesulfonic acid), wherein

the poly(3,4-ethylenedioxythiophene/styrenesulfonic acid) ~~the hole transport material being~~ is characterized in that when the hole transport material is dissolved or dispersed in a liquid so that its concentration becomes 2.0 wt %, the liquid contains nonionic impurities having a molecular weight of 5,000 or less, but an amount of the nonionic impurities contained therein is 40 ppm or less, and

the nonionic impurities consist essentially of a polyalcohol.

2. (Currently Amended) The hole transport material as claimed in claim 1, wherein the polyalcohol ~~nonionic impurities~~ mainly ~~include~~ includes those which are formed and/or mixed when synthesizing the poly(3,4-ethylenedioxythiophene/styrenesulfonic acid)~~hole transport material~~.

3-4. (Canceled)

5. (Currently Amended) The hole transport material as claimed in claim 1, wherein ~~the hold transport material contains a poly(thiophene/styrenesulfonate) based compound as its major component, and wherein when the hole transport material is dissolved or dispersed in a liquid so that its concentration thereof becomes 2.0 wt %, the liquid contains nonionic impurities having a molecular weight of 5,000 or less, but~~ an amount of the ~~nonionic impurities~~ polyalcohol contained in the liquid ~~therein~~ is six or less with respect to 1,000 styrene units.

6. (Currently Amended) The hole transport material as claimed in claim 5, wherein the number of the ~~nonionic impurities~~ polyalcohol and the number of the styrene units are measured from areas of peaks in a spectrum obtained by an ^{1}H-NMR analysis for the liquid.

7. (Currently Amended) The hole transport material as claimed in claim 5, wherein the ~~poly(thiophene/styrenesulfonate) based compound~~ poly(3,4-ethylenedioxythiophene/styrenesulfonic acid) has a weight ratio of ~~thiopene~~ thiophene to styrenesulfonate which is in the range of 1:5 to 1:50.

8. (Currently Amended) The ~~hold~~ hole transport material as claimed in claim 1, wherein the volume resistivity of the ~~hole transport material~~ poly(3,4-ethylenedioxythiophene/styrenesulfonic acid) is 10 Ω·cm or larger.

9. (Currently Amended) A layer having the function of transporting holes and provided in an organic EL device, wherein

the layer is characterized by containing nonionic impurities having a molecular weight of 5,000 or less, but an amount of the nonionic impurities is 2,000 ppm or less, and

the layer comprises poly(3,4-ethylenedioxythiophene/styrenesulfonic acid) and the nonionic impurities consist essentially of a polyalcohol.

10. (Currently Amended) A layer having the function of transporting holes and provided in an organic EL device, the layer comprising ~~being formed from~~poly(3,4-ethylenedioxythiophene/styrenesulfonic acid) ~~a hole transport material containing poly(thiophene/styrenesulfonate) based compound as its major component~~, wherein the layer contains nonionic impurities having a molecular weight of 5,000 or less, but an amount of the nonionic impurities contained therein is 6 or less with respect to 1000 styrene units, and

the nonionic impurities consist essentially of a polyalcohol.

11. (Currently Amended) The layer as claimed in claim 10, wherein the number of the ~~nonionic impurities~~ polyalcohol and the number of the styrene units are measured from areas of peaks in a spectrum obtained by an ^{1}H-NMR analysis for the layer.

12. (Canceled)

13. (Original) An organic EL device having a layer described in claim 9.

14. (Withdrawn) A method of manufacturing a hole transport material described in claim 1, the method comprising the steps of: preparing absolution or dispersion liquid in which the hole transport material is dissolved or dispersed in a solvent or a dispersion medium; separating or eliminating nonionic impurities having a molecular weight of 5,000 or less using an eliminating means for separating or eliminating the nonionic impurities; and removing the solvent or dispersion medium from the liquid, thereby refining the hole transport material.

15. (Withdrawn) The method of manufacturing a hole transport material as claimed in claim 14, wherein the eliminating means includes an ultrafiltration membrane.

16. (Currently Amended) A hole transport material to be used for a layer having the function of transporting holes in an organic EL device, the hole transport material being poly(3,4-ethylenedioxythiophene/styrenesulfonic acid), wherein the poly(3,4-ethylenedioxythiophene/styrenesulfonic acid) ~~the hole transport material being~~ is characterized in that when the ~~hole transport material~~ poly(3,4-ethylenedioxythiophene/styrenesulfonic acid) is dissolved or dispersed in a liquid so that its concentration becomes 2.0 wt %, the liquid contains anionic impurities, cationic impurities and nonionic impurities having a molecular weight of 5,000 or less, but amounts of the anionic impurities, cationic impurities and nonionic impurities contained therein are 30 ppm or less, 30 ppm or less and 40 ppm or less, respectively, and

wherein the nonionic impurities consist essentially of a polyalcohol.

17. (Currently Amended) The hole transport material as claimed in claim 16, wherein ~~when the hole transport material is dissolved or dispersed in a liquid so that its concentration becomes 2.0 wt %,~~ the total amount of the anionic impurities, cationic impurities and ~~nonionic impurities~~ the polyalcohol contained ~~therein~~ in the liquid is 90 ppm or less.

18. (Original) The hole transport material as claimed in claim 16, wherein the anionic impurities include at least one of sulfate ion, formate ion, oxalate ion and acetate ion.

19. (Original) The hole transport material as claimed in claim 16, wherein the cationic impurities mainly include metal ion.

20. (Original) The hole transport material as claimed in claim 19, wherein the metal ion includes at least one kind of metal ions of metals belonging to Ia group, IIa group, VIa group, VIIa group, VIII group and IIb group of the periodic table.

21. (Currently Amended) The hole transport material as claimed in claim 16, wherein the ~~nonionic impurities~~ polyalcohol mainly ~~include~~includes those which are formed and/or mixed when synthesizing the ~~hole transport material~~ poly(3,4-ethylenedioxythiophene/styrenesulfonic acid).

22. (Canceled)

23. (Currently Amended) The ~~hold~~ hole transport material as claimed in claim 16, wherein the volume resistivity of the ~~hole transport material~~ poly(3,4-ethylenedioxythiophene/styrenesulfonic acid) is 10 Ω·cm or larger.

24-25. (Canceled)

26. (Currently Amended) The hole transport material as claimed in ~~claim 25~~ claim 16, wherein the ~~poly(thiophene/styrenesulfonate) based compound~~ poly(3,4-ethylenedioxythiophene/styrenesulfonic acid) has a weight ratio of ~~thiopene~~ thiophene to styrenesulfonate which is in the range of 1:5 to 1:50

27. (Currently Amended) A layer having the function of transporting holes and provided in an organic EL device, wherein the layer is characterized by containing anionic impurities, cationic impurities and nonionic impurities having a molecular weight of 5,000 or less, but amounts of the anionic impurities, cationic impurities and nonionic impurities are 1,500 ppm or less, 1500 ppm or less and 2,000 ppm or less, respectively,

wherein the layer comprises poly(3,4-ethylenedioxythiophene/styrenesulfonic acid) and the nonionic impurities consist essentially of a polyalcohol.

28. (Currently Amended) The layer as claimed in claim 27, wherein the total amount of the anionic impurities, cationic impurities and ~~nonionic impurities~~ the polyalcohol is 4,500 ppm or less.

29. (Canceled)

30. (Original) An organic EL device having a layer described in claim 27.

31. (Withdrawn) A method of manufacturing a hole transport material described in claim 16, the method comprising the steps of: preparing a solution or dispersion liquid in which the hole transport material is dissolved or dispersed in a solvent or a dispersion medium; separating or eliminating anionic impurities, cationic impurities and nonionic impurities having a molecular weight of 5,000 or less using a first eliminating means for separating or eliminating the anionic impurities, a second eliminating means for separating or eliminating the cationic impurities, and a third eliminating means for separating or eliminating the nonionic impurities at substantially the same time or successively; and removing the solvent or dispersion medium from the liquid, thereby refining the hole transport material.

32. (Withdrawn) The method of manufacturing a hole transport material as claimed in claim 31, wherein the third eliminating means includes an ultrafiltration membrane.

33. (New) The hole transport material as claimed in claim 1, wherein the polyalcohol is ethylene glycol, and the amount of the ethylene glycol included in the liquid is 1.95 to 40 ppm.

34. (New) The hole transport material as claimed in claim 16, wherein the polyalcohol is ethylene glycol, and the amount of the ethylene glycol included in the liquid is 1.95 to 40 ppm.

35. (New) The hole transport material as claimed in claim 16, wherein the anionic impurities include a sulfate ion, a formate ion, an oxalate ion, and an acetate ion, and the amounts of the sulfate ion, the formate ion, the oxalate ion, and the acetate ion included in the liquid are 7.8 to 16.9 ppm, 0.7 to 2.4 ppm, 0.2 to 1.3 ppm, and 0.1 to 1.3 ppm, respectively.

36. (New) The hole transport material as claimed in claim 16, wherein the cationic impurities include at least one of a Na ion, a Mg ion, a K ion, a Ca ion, a Cr ion, a Mn ion, a Fe ion, a Ni ion, a Zn ion, and a Sr ion, and the amount of the cationic impurities included in the liquid are 1 to 30 ppm.